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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/692,093	10/22/2003	Jinru Bian	02005US	8299

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EXAMINER

CHEN, ERIC BRICE

ART UNIT	PAPER NUMBER
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1765

DATE MAILED: 07/12/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

Office Action Summary

Application No.

10/692,093

Applicant(s)

BIAN, JINRU

Examiner

Eric B. Chen

Art Unit

1765

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --
Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

Status

- 1) ☒ Responsive to communication(s) filed on 22 October 2003.
2a) ☐ This action is FINAL. 2b) ☒ This action is non-final.
3) ☐ Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

Disposition of Claims

- 4) ☒ Claim(s) 1-10 is/are pending in the application.
4a) Of the above claim(s) 10 is/are withdrawn from consideration.
5) ☐ Claim(s) _____ is/are allowed.
6) ☒ Claim(s) 1-9 is/are rejected.
7) ☐ Claim(s) _____ is/are objected to.
8) ☒ Claim(s) 1-10 are subject to restriction and/or election requirement.

Application Papers

- 9) ☐ The specification is objected to by the Examiner.
10) ☐ The drawing(s) filed on _____ is/are: a) ☐ accepted or b) ☐ objected to by the Examiner.
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).
11) ☐ The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

Priority under 35 U.S.C. § 119

- 12) ☐ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
a) ☐ All b) ☐ Some * c) ☐ None of:
1. ☐ Certified copies of the priority documents have been received.
2. ☐ Certified copies of the priority documents have been received in Application No. _____.
3. ☐ Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).

* See the attached detailed Office action for a list of the certified copies not received.

Attachment(s)

- 1) ☒ Notice of References Cited (PTO-892)
2) ☐ Notice of Draftsperson's Patent Drawing Review (PTO-948)
3) ☒ Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08)
Paper No(s)/Mail Date 2/27/04; 4/7/05
4) ☐ Interview Summary (PTO-413)
Paper No(s)/Mail Date. _____
5) ☐ Notice of Informal Patent Application (PTO-152)
6) ☐ Other: _____

DETAILED ACTION

Election/Restrictions

1. Restriction to one of the following inventions is required under 35 U.S.C. 121:
 - I. Claims 1-9, drawn to a polishing method, classified in class 438, subclass 690.
 - II. Claim 10, drawn to a polishing fluid, classified in class 252, subclass 79.1.
2. The inventions are distinct, each from the other because of the following reasons: Inventions I and II are related as product and process of use. The inventions can be shown to be distinct if either or both of the following can be shown: (1) the process for using the product as claimed can be practiced with another materially different product or (2) the product as claimed can be used in a materially different process of using that product (MPEP § 806.05(h)). In the instant case, the polishing fluid can be used to polish, etch or clean any article and not limited to semiconductor wafers.
3. Because these inventions are distinct for the reasons given above and have acquired a separate status in the art as shown by their different classification, restriction for examination purposes as indicated is proper. Furthermore, because these inventions are distinct for the reasons given above and the search required for Invention I is not required for Invention II, restriction for examination purposes as indicated is proper.
4. During a telephone conversation with Blake T. Biederman on June 21, 2005, a provisional election was made with traverse to prosecute Invention I, claims 1-9.

Art Unit: 1765

Affirmation of this election must be made by applicant in replying to this Office action.

Claim 10 is withdrawn from further consideration by the examiner, 37 CFR 1.142(b), as being drawn to a non-elected invention.

Priority

5. Applicant is advised of possible benefits under 35 U.S.C. 119(a)-(d), wherein an application for patent filed in the United States may be entitled to the benefit of the filing date of a prior application filed in a foreign country.

Claim Rejections - 35 USC § 102

6. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless –

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

7. Claims 1-9 are rejected under 35 U.S.C. 102(b) as being anticipated by Tsuchiya et al. (U.S. Patent Appl. Pub. No. 2001/0006224).

8. As to claim 1, Tsuchiya discloses method for removal of a barrier film on a semiconductor wafer by polishing with a polishing pad and a polishing fluid (paragraph 0058), the polishing fluid comprising abrasive particles in the range of 0.1% to 5% by weight (paragraph 0028) and an organic acid or mixture thereof in the range of 0.5-10% by weight (paragraph 0050) in an aqueous solution at basic pH (paragraph 0043).

Tsuchiya discloses that an oxidizing agent may be added to the polishing slurry

Art Unit: 1765

(paragraph 0045). Therefore, the oxidizing agent is optional and includes an embodiment with no addition of an oxidizing agent.

9. As to claim 2, Tsuchiya discloses that the organic acid is selected from the group consisting of carboxylic acids, hydrocarboxylic acids containing a hydroxyl group, and amino acids (paragraph 0046).

10. As to claim 3, Tsuchiya discloses that the organic acid is selected from the group consisting of citric acid, maleic acid, formic acid, acetic acid, propionic acid, butyric acid, valeric acid, acrylic acid, lactic acid, succinic acid malic acid, malonic acid, succinic acid, tartaric acid, phthalic acid, fumaric acid, lactic acid (α -hydroxypropionic acid or β -hydroxypropionic acid), pimelic acid, adipic acid, glutaric acid, oxalic acid, salicylic acid, glycolic acid, tricarballic acid, and benzoic acid (paragraph 0047).

11. As to claim 4, Tsuchiya discloses that the amino acid is selected from the group consisting of glutamic acid, glutamic acid hydrochloride, sodium glutamate monohydrate, glutamine, glutathione, glycylglycine, alanine, β -alanine, γ -aminobutyric acid, ϵ -aminocaproic acid, lysine, lysine hydrochloride, lysine dihydrochloride, lysine picrate, histidine, histidine hydrochloride, histidine dihydrochloride, aspartic acid, aspartic acid monohydrate, potassium aspartate, potassium aspartate trihydrate, tryptophan, threonine, glycine, cystine, cysteine, cysteine hydrochloride monohydrate, oxyproline, isoleucine, leucine, methionine, ornithine hydrochloride, phenylalanine, phenylglycine, proline, serine, tyrosine, valine, and a mixture of these amino acids (paragraph 0049).

Art Unit: 1765

12. As to claim 5, Tsuchiya discloses that the said abrasive is silicon dioxide (paragraph 0028).
13. As to claim 6, Tsuchiya discloses that the organic acid is citric acid (paragraph 0047).
14. As to claim 7, Tsuchiya discloses that the amino acid is glutamic acid (paragraph 0049).
15. As to claim 8, Tsuchiya discloses that a metal corrosion inhibitor (or antioxidant) is added to said polishing solution (paragraph 0053).
16. As to claim 9, Tsuchiya discloses that the fluid pH is in the range from pH 7 to pH 11 (paragraph 0043).

Claim Rejections - 35 USC § 103

17. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negated by the manner in which the invention was made.

18. Claims 1-9 are rejected under 35 U.S.C. 103(a) as being unpatentable over Tsuchiya.
19. As to claim 1, Tsuchiya discloses method for removal of a barrier film on a semiconductor wafer by polishing with a polishing pad and a polishing fluid (paragraph 0058), the polishing fluid comprising abrasive particles in the range of 0.1% to 5% by

Art Unit: 1765

weight (paragraph 0028) and an organic acid or mixture thereof in the range of 0.5-10% by weight (paragraph 0050) in an aqueous solution at basic pH (paragraph 0043).

20. Tsuchiya does not expressly disclose that there is no addition of an oxidizing agent. Tsuchiya teaches that the oxidizing agent enhances polishing of the conductive metal (paragraph 0045). Moreover, Tsuchiya discloses that an oxidizing agent may be added to the polishing slurry (paragraph 0045) and thus, the oxidizing agent is optional and includes an embodiment with no addition of an oxidizing agent. Therefore, it would have been obvious to one of ordinary skill in the art at the time the invention was made to mix a polishing fluid with no addition of an oxidizing agent. One who is skilled in the art would be motivated to mix a solution with only the necessary additives.

21. As to claim 2, Tsuchiya discloses that the organic acid is selected from the group consisting of carboxylic acids, hydrocarboxylic acids containing a hydroxyl group, and amino acids (paragraph 0046).

22. As to claim 3, Tsuchiya discloses that the organic acid is selected from the group consisting of citric acid, maleic acid, formic acid, acetic acid, propionic acid, butyric acid, valeric acid, acrylic acid, lactic acid, succinic acid malic acid, malonic acid, succinic acid, tartaric acid, phthalic acid, fumaric acid, lactic acid (α -hydroxypropionic acid or β -hydroxypropionic acid), pimelic acid, adipic acid, glutaric acid, oxalic acid, salicylic acid, glycolic acid, tricarballic acid, and benzoic acid (paragraph 0047).

23. As to claim 4, Tsuchiya discloses that the amino acid is selected from the group consisting of glutamic acid, glutamic acid hydrochloride, sodium glutamate monohydrate, glutamine, glutathione, glycylglycine, alanine, β -alanine, γ -aminobutyric

Art Unit: 1765

acid, ϵ -aminocarproic acid, lysine, lysine hydrochloride, lysine dihydrochloride, lysine picrate, histidine, histidine hydrochloride, histidine dihydrochloride, aspartic acid, aspartic acid monohydrate, potassium aspartate, potassium aspartate trihydrate, tryptophan, threonine, glycine, cystine, cysteine, cysteine hydrochloride monohydrate, oxyproline, isoleucine, leucine, methionine, omithine hydrochloride, phenylalanine, phenylglycine, proline, serine, tyrosine, valine, and a mixture of these amino acids (paragraph 0049).

24. As to claim 5, Tsuchiya discloses that the said abrasive is silicon dioxide (paragraph 0028).

25. As to claim 6, Tsuchiya discloses that the organic acid is citric acid (paragraph 0047).

26. As to claim 7, Tsuchiya discloses that the amino acid is glutamic acid (paragraph 0049).

27. As to claim 8, Tsuchiya discloses that a metal corrosion inhibitor (or antioxidant) is added to said polishing solution (paragraph 0053).

28. As to claim 9, Tsuchiya discloses that the fluid pH is in the range from pH 7 to pH 11 (paragraph 0043).

Conclusion

29. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. Kakizawa et al. (U.S. Patent Appl. Pub. No. 2003/0083214)

Art Unit: 1765

discloses a semiconductor surface cleaning agent with a basic pH, a silica abrasive, citric acid, glutamic acid, and a corrosion inhibitor.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Eric B. Chen whose telephone number is (571) 272-2947. The examiner can normally be reached on Monday through Friday, 8AM to 4:30PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nadine G. Norton can be reached on (571) 272-1465. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

EBC

June 24, 2005



NADINE G. NORTON
SUPERVISORY PATENT EXAMINER

